

## ERRATUM: PREDICTION OF DISLOCATION NUCLEATION DURING NANOINDENTATION BY THE ORBITAL-FREE DENSITY FUNCTIONAL THEORY LOCAL QUASI-CONTINUUM METHOD\*

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**Abstract.** In this erratum, we correct typographical errors in the equation for the ion-electron stress in [Hayes et al., *Multiscale Model. Simul.*, 4 (2005), pp. 359–389].

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In [1], (A.3) should have been written

$$\sigma_{\alpha\beta}^{\text{Ext}} = -\frac{1}{\Omega} \sum_{g \neq 0} \sum_I \rho(\vec{g}) \frac{g_\alpha g_\beta}{|\vec{g}|} \frac{\partial V_{Ie,I}^{\text{loc}}(g)}{\partial g} \exp(i\vec{g} \cdot \vec{R}_I) - \delta_{\alpha\beta} \frac{E_{\text{Ext}}}{\Omega}.$$

The above (correct) equation, previously derived by Nielsen and Martin [2], was used during all of the simulations reported in this work.

### REFERENCES

- [1] R. L. HAYES, M. FAGO, M. ORTIZ, AND E. A. CARTER, *Prediction of dislocation nucleation during nanoindentation by the orbital-free density functional theory local quasi-continuum method*, *Multiscale Model. Simul.*, 4 (2005), pp. 359–389.
- [2] O. H. NIELSEN AND R. M. MARTIN, *Stresses in semiconductors: Ab initio calculations on Si, Ge, and GaAs*, *Phys. Rev. B*, 32 (1985), pp. 3792–3805.

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